

L Number	Hits	Search Text	DB	Time stamp
1	51612	(rta rtp rto anneal annealing annealed anneals annealling annealled heat heated heating bake baking baked) near15 (infra-red infrared IR)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/17 11:46
8	348566	(rta rtp rto anneal annealing annealed anneals annealling annealled heat heated heating bake baking baked) near10 (oxide dioxide dielectric insulator insulating insulation isolation isolating isolator)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/17 11:47
15	93	((rta rtp rto anneal annealing annealed anneals annealling annealled heat heated heating bake baking baked) near15 (infra-red infrared IR)) and "7"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/17 11:47
22	9025	((rta rtp rto anneal annealing annealed anneals annealling annealled heat heated heating bake baking baked) near15 (infra-red infrared IR)) and ((rta rtp rto anneal annealing annealed anneals annealling annealled heat heated heating bake baking baked) near10 (oxide dioxide dielectric insulator insulating insulation isolation isolating isolator))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/17 11:47
29	4908	TEOS same (plasma RF (glow adj discharge))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/17 11:48
36	232	((((rta rtp rto anneal annealing annealed anneals annealling annealled heat heated heating bake baking baked) near15 (infra-red infrared IR)) and ((rta rtp rto anneal annealing annealed anneals annealling annealled heat heated heating bake baking baked) near10 (oxide dioxide dielectric insulator insulating insulation isolation isolating isolator))) and (TEOS same (plasma RF (glow adj discharge)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/17 11:48
43	3	(((((rta rtp rto anneal annealing annealed anneals annealling annealled heat heated heating bake baking baked) near15 (infra-red infrared IR)) and ((rta rtp rto anneal annealing annealed anneals annealling annealled heat heated heating bake baking baked) near10 (oxide dioxide dielectric insulator insulating insulation isolation isolating isolator))) and (TEOS same (plasma RF (glow adj discharge)))) and @ad<19930825	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/17 12:20
50	13	(((((rta rtp rto anneal annealing annealed anneals annealling annealled heat heated heating bake baking baked) near15 (infra-red infrared IR)) and ((rta rtp rto anneal annealing annealed anneals annealling annealled heat heated heating bake baking baked) near10 (oxide dioxide dielectric insulator insulating insulation isolation isolating isolator))) and (TEOS same (plasma RF (glow adj discharge)))) and @rlad<19930825	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/17 11:49
57	14	(((((rta rtp rto anneal annealing annealed anneals annealling annealled heat heated heating bake baking baked) near15 (infra-red infrared IR)) and ((rta rtp rto anneal annealing annealed anneals annealling annealled heat heated heating bake baking baked) near10 (oxide dioxide dielectric insulator insulating insulation isolation isolating isolator))) and (TEOS same (plasma RF (glow adj discharge)))) and @ad<19930825) (((((rta rtp rto anneal annealing annealed anneals annealling annealled heat heated heating bake baking baked) near15 (infra-red infrared IR)) and ((rta rtp rto anneal annealing annealed anneals annealling annealled heat heated heating bake baking baked) near10 (oxide dioxide dielectric insulator insulating insulation isolation isolating isolator))) and (TEOS same (plasma RF (glow adj discharge)))) and @rlad<19930825)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/17 12:15

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64	1602	(TEOS alkoxysilane tetraethylorthosilicate (tetra adj3 (ethylorthosilicate orthosilicate silicate ethoxysilane (ethoxy adj silane)))) same (gate adj (oxide dioxide dielectric insulator insulating insulation isolation isolating isolator))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/17 12:20
71	779	(TEOS same (plasma RF (glow adj discharge))) and ((TEOS alkoxysilane tetraethylorthosilicate (tetra adj3 (ethylorthosilicate orthosilicate silicate ethoxysilane (ethoxy adj silane)))) same (gate adj (oxide dioxide dielectric insulator insulating insulation isolation isolating isolator)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/17 12:20
78	34	((TEOS same (plasma RF (glow adj discharge))) and ((TEOS alkoxysilane tetraethylorthosilicate (tetra adj3 (ethylorthosilicate orthosilicate silicate ethoxysilane (ethoxy adj silane)))) same (gate adj (oxide dioxide dielectric insulator insulating insulation isolation isolating isolator)))) and @ad<19930825	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/17 12:20
85	35	((TEOS same (plasma RF (glow adj discharge))) and ((TEOS alkoxysilane tetraethylorthosilicate (tetra adj3 (ethylorthosilicate orthosilicate silicate ethoxysilane (ethoxy adj silane)))) same (gate adj (oxide dioxide dielectric insulator insulating insulation isolation isolating isolator)))) and @rlad<19930825	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/17 12:20
92	59	((((TEOS same (plasma RF (glow adj discharge))) and ((TEOS alkoxysilane tetraethylorthosilicate (tetra adj3 (ethylorthosilicate orthosilicate silicate ethoxysilane (ethoxy adj silane)))) same (gate adj (oxide dioxide dielectric insulator insulating insulation isolation isolating isolator)))) and @ad<19930825) (((TEOS same (plasma RF (glow adj discharge))) and ((TEOS alkoxysilane tetraethylorthosilicate (tetra adj3 (ethylorthosilicate orthosilicate silicate ethoxysilane (ethoxy adj silane)))) same (gate adj (oxide dioxide dielectric insulator insulating insulation isolation isolating isolator)))) and @rlad<19930825)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/17 12:20